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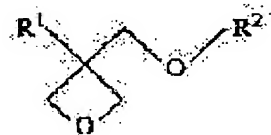
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## (54) ACTIVE ENERGY RAY CURING TYPE COMPOSITION FOR COATING PLASTICS

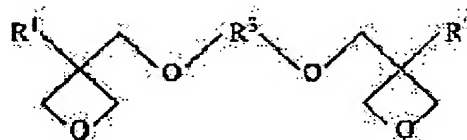
## (57)Abstract:

PURPOSE: To obtain the subject composition, comprising a specific compound containing the oxetane ring and a cationic photopolymerization initiator, having a high curing rate, excellent in adhesion, scuff resistance and surface smoothness of a film and useful for hard coating of a plastics.

CONSTITUTION: This composition comprises (A) a compound having 1-4 oxetane rings [e.g. a compound of formula I [R<sup>1</sup> is H, a 1-6C (fluoro)alkyl, allyl, etc.; R<sup>2</sup> is a 1-6C alkyl, a 2-6C alkenyl, phenyl, etc.] or a compound of formula II [R<sup>3</sup> is a (branched) alkylene, a (branched) poly(alkyleneoxy), a bivalent unsaturated hydrocarbon group, etc.]] and (B) a cationic photopolymerization initiator (e.g. a diaryliodonium salt or a triarylsulfonium salt) and, as necessary, further (C) a compound containing epoxy group, (D) a compound containing vinyl ether group or (E) a compound containing (meth)acryloyl group and a photopolymerization free radical initiator.



I



II

## LEGAL STATUS

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